



PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q60206

Toshiaki AOAI, et al.

Appln. No.: 09/620,708

Group Art Unit: 1752

Confirmation No.: 3362

Examiner: J. Chu

Filed: July 20, 2000

RECEIVED
DEC 04 2003
TC 1700

For: POSITIVE PHOTORESIST COMPOSITION FOR FAR ULTRAVIOLET
EXPOSURE

RESPONSE UNDER 37 C.F.R. § 1.111

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

This Amendment is submitted in response to the Office Action dated May 21, 2003. A Petition for a three month extension of time is being concurrently filed, making a response due on or before November 21, 2003. A Terminal Disclaimer is also concurrently filed herewith. Please enter and consider the following Remarks.

REMARKS

Claims 1-25 are all the claims pending in the application.